

## Supporting Information

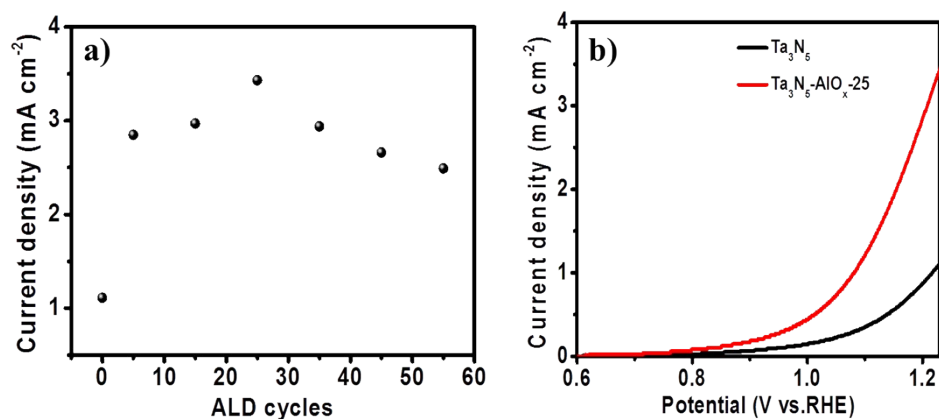
### **Interface Engineering with $\text{AlO}_x$ dielectric layer enabling an ultrastable $\text{Ta}_3\text{N}_5$ photoanode for photoelectrochemical water oxidation**

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**Fig. S1** a) Current density of Ta<sub>3</sub>N<sub>5</sub> photoanodes modified with different thickness of AlO<sub>x</sub> layer at 1.23 V vs. RHE under AM 1.5G simulated sunlight at 100 mW cm<sup>-2</sup> in the 1 M NaOH aqueous solution (pH = 13.6). b) Current-potential curves of Ta<sub>3</sub>N<sub>5</sub>, Ta<sub>3</sub>N<sub>5</sub>-AlO<sub>x</sub>-25 photoanodes at 1.23V vs. RHE under AM 1.5G simulated sunlight at 100 mW cm<sup>-2</sup> in the 1 M NaOH aqueous solution (pH = 13.6).

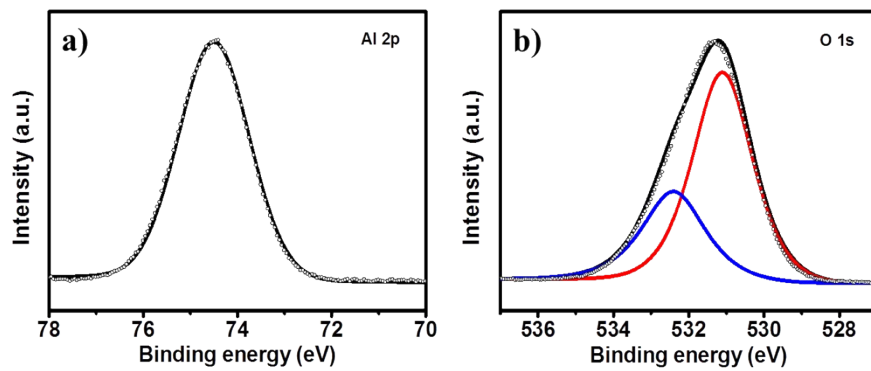
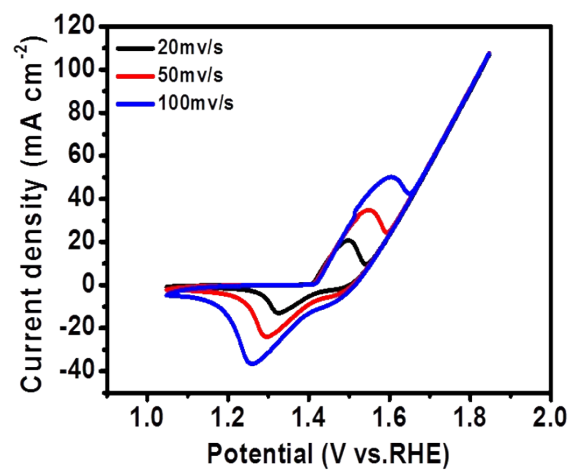
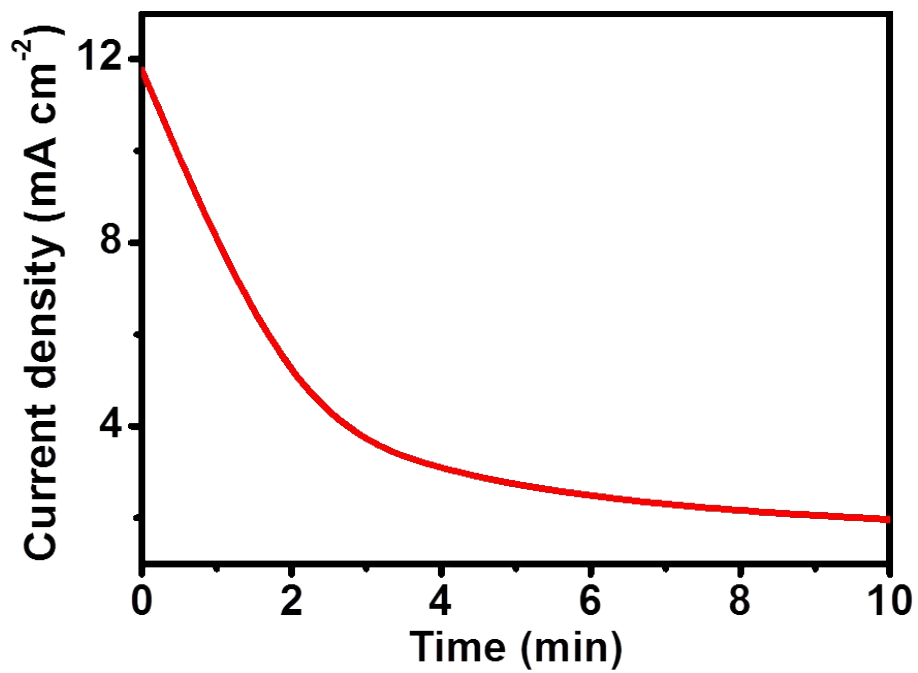


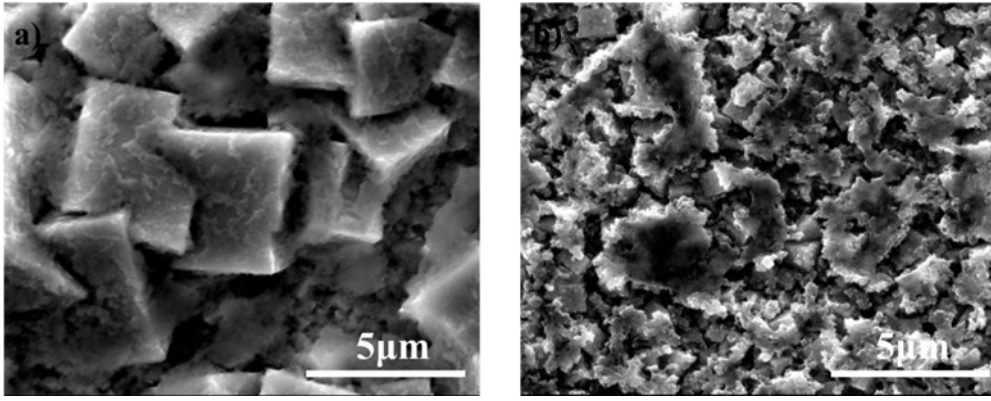
Fig. S2 a) XPS spectra of Al 2p for Ta<sub>3</sub>N<sub>5</sub>-AlO<sub>x</sub> photoanode. b) XPS spectra of O 1s for Ta<sub>3</sub>N<sub>5</sub>-AlO<sub>x</sub> photoanode.



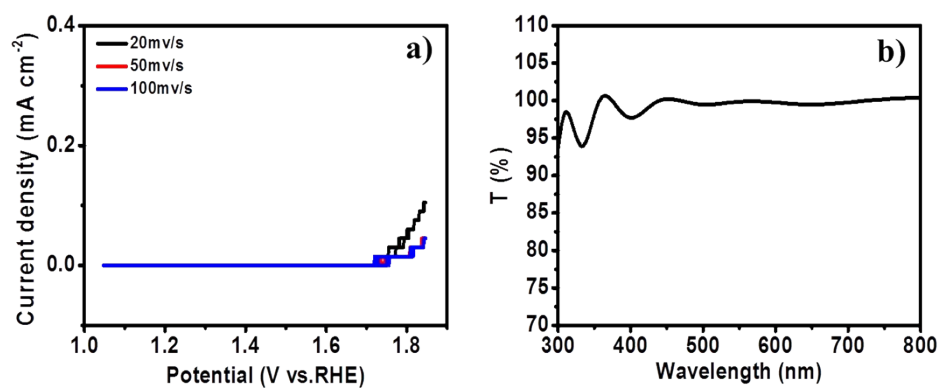
**Fig. S3** Cyclic voltammogram measurements for NiFeO<sub>x</sub> cocatalyst on FTO under scan rates of 20, 50, 100 mV s<sup>-1</sup> in 1 M NaOH aqueous solution (pH = 13.6).



**Fig. S4** Chronoamperometry measurement of  $\text{Ta}_3\text{N}_5\text{-AlO}_x\text{-Fh-NiFeO}_x$  photoanode under AM 1.5G simulated sunlight at 1.23V in 1 M NaOH aqueous solution (pH = 13.6).



**Fig. S5** a) The SEM image of  $\text{Ta}_3\text{N}_5\text{-AlO}_x\text{-Fh-NiFeO}_x$  photoanode. b) The SEM image of  $\text{Ta}_3\text{N}_5\text{-AlO}_x\text{-Fh-NiFeO}_x$  photoanode after stability test for 10min.



**Fig. S6** a) Cyclic voltammogram measurements for CeO<sub>x</sub> film on FTO under scan rates of 20, 50, 100 mVs<sup>-1</sup>. b) Light transmittance test for CeO<sub>x</sub> film on FTO.

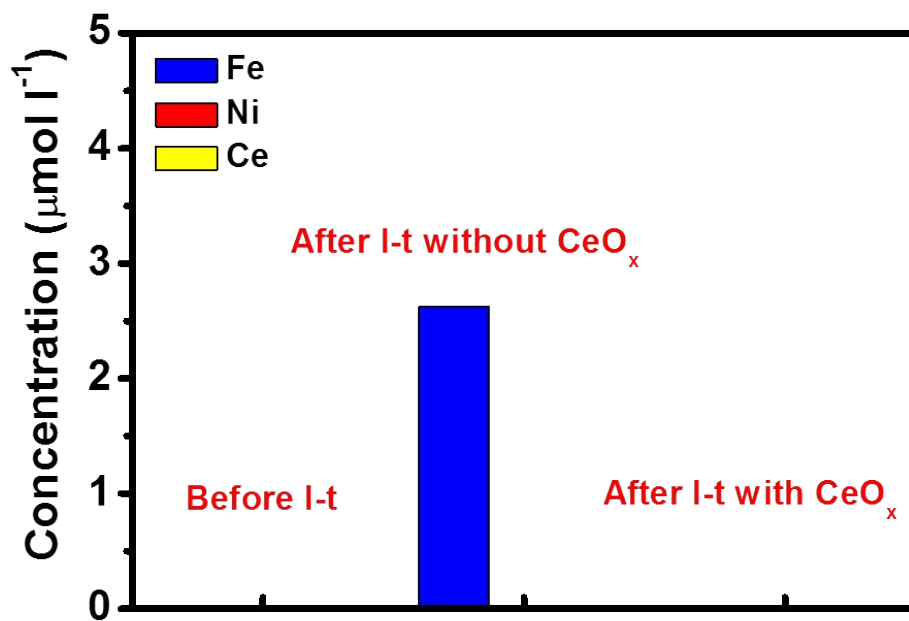


Fig. S7 ICP-OES analysis of NaOH solution before and after J-t measurement.



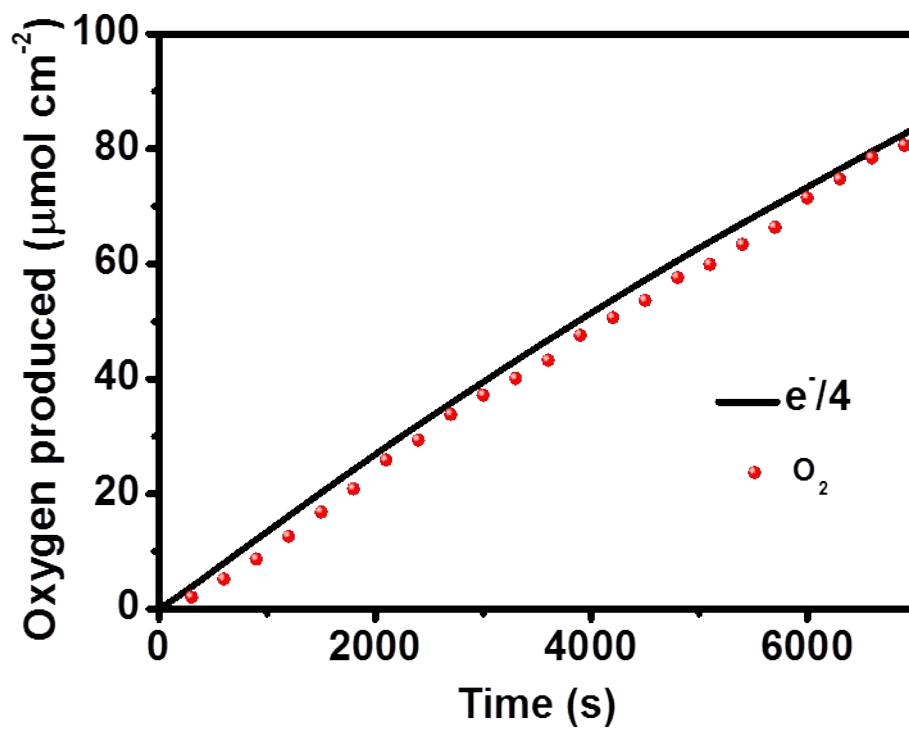
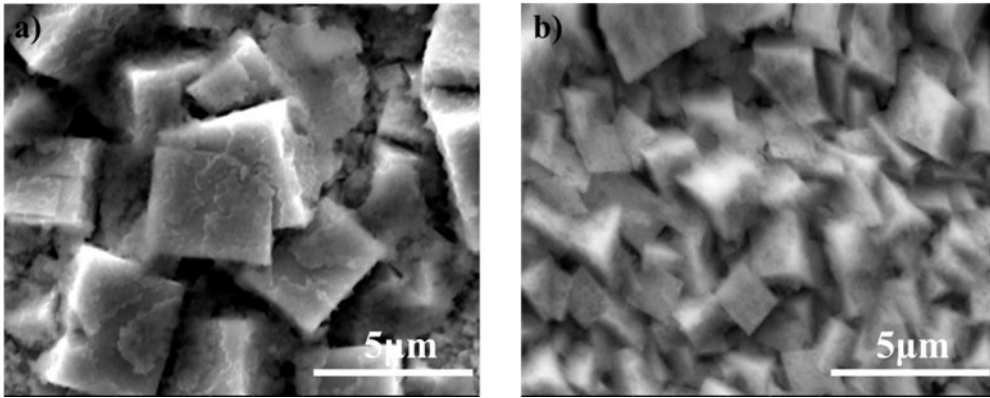
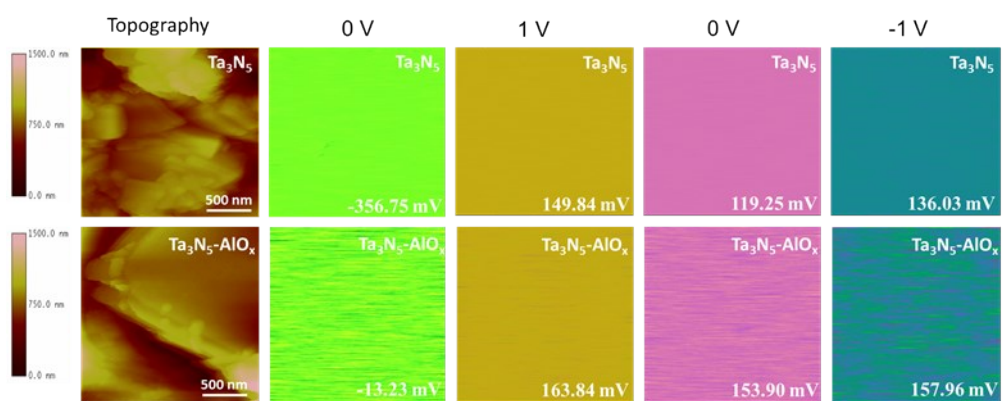


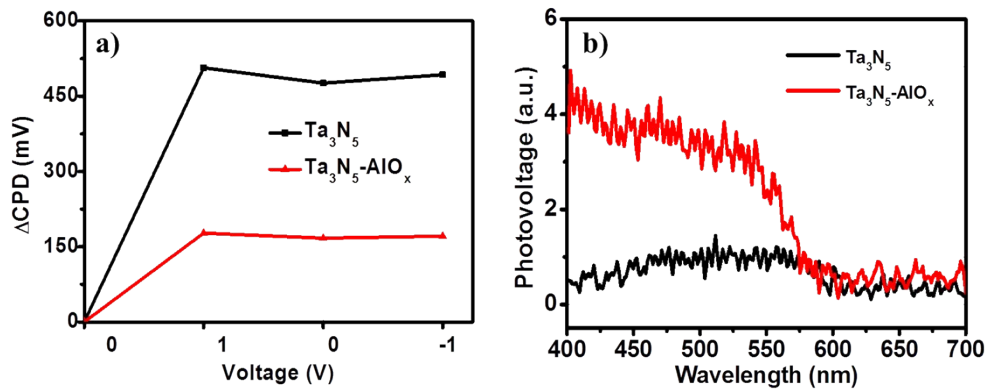
Fig. S8 Oxygen evolution measurement of the  $\text{Ta}_3\text{N}_5\text{-AlO}_x\text{-Fh-NiFeO}_x\text{-CeO}_x$  photoanode at 1.23 V in 1 M NaOH aqueous solution (pH = 13.6).



**Fig. S9** a) The SEM image of  $\text{Ta}_3\text{N}_5\text{-AlO}_x\text{-Fh-NiFeO}_x\text{-CeO}_x$  photoanode. b) The SEM image of  $\text{Ta}_3\text{N}_5\text{-AlO}_x\text{-Fh-NiFeO}_x\text{-CeO}_x$  photoanode after stability test for 120 hours.

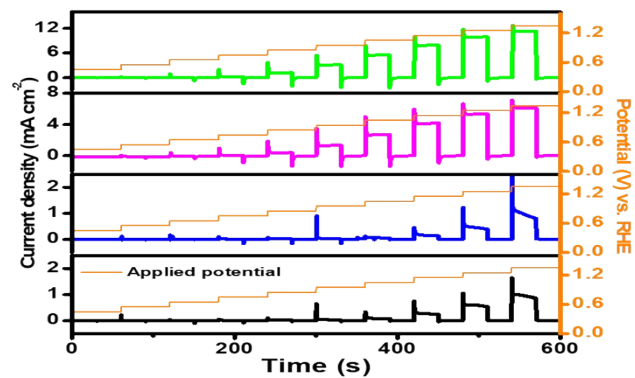


**Fig. S10** Topography and CPD map of the Ta<sub>3</sub>N<sub>5</sub> and Ta<sub>3</sub>N<sub>5</sub>-AlO<sub>x</sub> photoanodes with different bias voltage in the dark.



**Fig. S11** a)  $\Delta$ CPD values as a function of bias voltage applied to the tip. b) SPV responses of Ta<sub>3</sub>N<sub>5</sub>, Ta<sub>3</sub>N<sub>5</sub>-AlO<sub>x</sub> photoanodes.

Kelvin probe force microscopy was also performed to further clarify the role of AlO<sub>x</sub> layer. Different bias voltage of -1, 0, and 1 V were applied at the atomic force microscopy (AFM) tip in dark (Fig. S7) and contact potential difference (CPD) can be detected. Fig. S11a shows  $\Delta$ CPD value of the sample with AlO<sub>x</sub> layer is significantly lower than that of reference sample by about 400 mV, which shows that the interface trap states can be passivated.  $\Delta$ CPD increased for both the samples at a bias of +1 V and -1 V, but the change rate is higher for control samples. In addition,  $\Delta$ CPD value tends to be saturated after AlO<sub>x</sub> layer modification, rather than fluctuating obviously with bias voltage changes. This indicates that the trap states of samples seem to be less sensitive to the electric field with AlO<sub>x</sub> dielectric layer. Accordingly, the AlO<sub>x</sub> dielectric layer can effectively passivate trap states of Ta<sub>3</sub>N<sub>5</sub> photoanode, which corresponds to the result in Fig. 3. This is also confirmed by surface photovoltage spectroscopy (SPV) measurement results. As shown in Fig. S11b, the SPV response of Ta<sub>3</sub>N<sub>5</sub>-AlO<sub>x</sub> photoanode is significantly higher than that of pristine one.



**Fig. S12** Chopped light chronoamperometry measurements of  $\text{Ta}_3\text{N}_5$  (black curve),  $\text{Ta}_3\text{N}_5\text{-AlO}_x$  (blue curve),  $\text{Ta}_3\text{N}_5\text{-Fh}$  (pink curve),  $\text{Ta}_3\text{N}_5\text{-AlO}_x\text{-Fh}$  (green curve) photoanodes in the 1 M NaOH aqueous solution (pH = 13.6). The potential is scanned from 0.45 to 1.45 V vs. RHE with a 0.1 V step and with a 60 s light on/off cycle on each step.

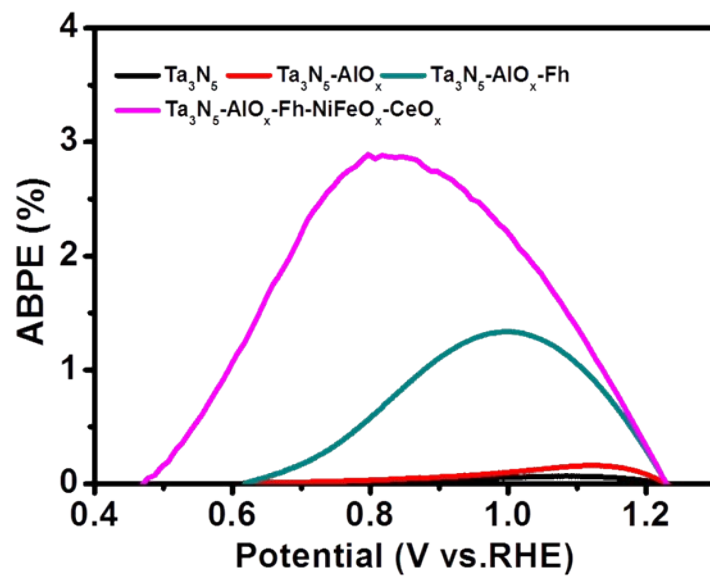
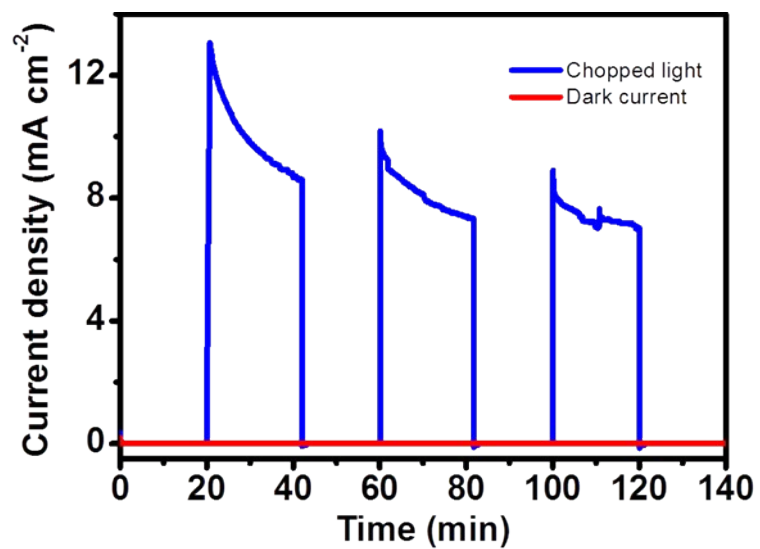
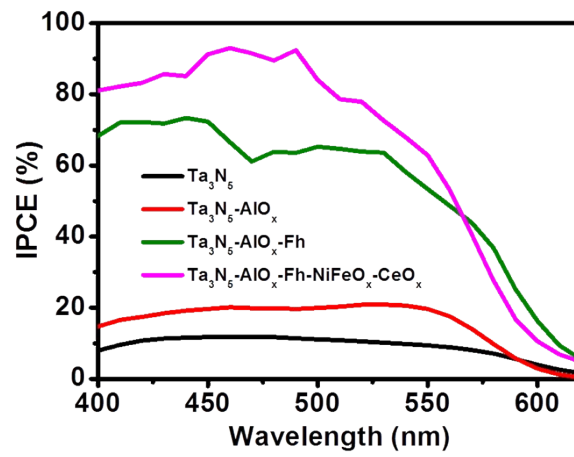


Fig. S13 The applied bias photon-to-current efficiency (ABPE) of  $\text{Ta}_3\text{N}_5$ ,  $\text{Ta}_3\text{N}_5\text{-AlO}_x$ ,  $\text{Ta}_3\text{N}_5\text{-AlO}_x\text{-Fh}$ ,  $\text{Ta}_3\text{N}_5\text{-AlO}_x\text{-Fh-NiFeO}_x\text{-CeO}_x$  photoanodes.

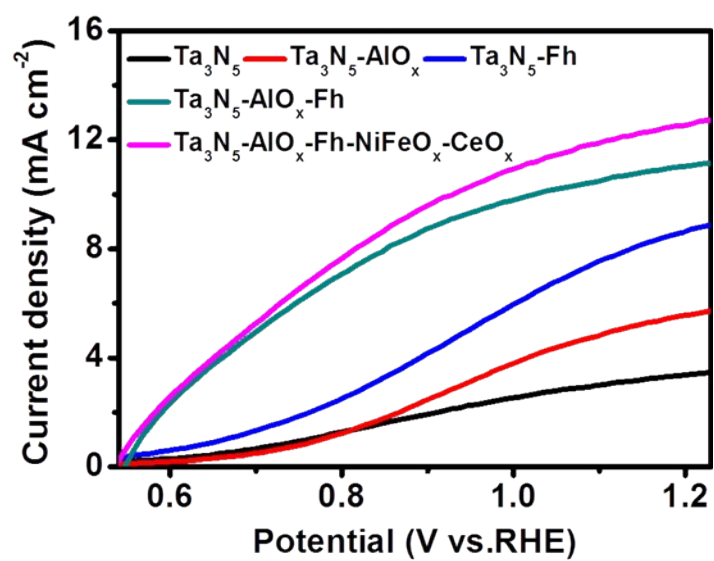


**Fig. S14** The corresponding dark current and chopped light chronoamperometry measurement of Ta<sub>3</sub>N<sub>5</sub>-AlO<sub>x</sub>-Fh-NiFeO<sub>x</sub>-CeO<sub>x</sub> at 1.23 V in 1 M NaOH solution.



**Fig. S15** IPCE curves of Ta<sub>3</sub>N<sub>5</sub>, Ta<sub>3</sub>N<sub>5</sub>-AlO<sub>x</sub>, Ta<sub>3</sub>N<sub>5</sub>-AlO<sub>x</sub>-Fh, Ta<sub>3</sub>N<sub>5</sub>-AlO<sub>x</sub>-Fh-NiFeO<sub>x</sub>-CeO<sub>x</sub> photoanodes at 1.23 V in 1 M NaOH solution.





**Fig. S16** Current-potential curves of Ta<sub>3</sub>N<sub>5</sub>, Ta<sub>3</sub>N<sub>5</sub>-AlO<sub>x</sub>, Ta<sub>3</sub>N<sub>5</sub>-Fh, Ta<sub>3</sub>N<sub>5</sub>-AlO<sub>x</sub>-Fh, Ta<sub>3</sub>N<sub>5</sub>-AlO<sub>x</sub>-Fh-NiFeO<sub>x</sub>-CeO<sub>x</sub> photoanodes in 1 M NaOH-0.5M H<sub>2</sub>O<sub>2</sub> solution.

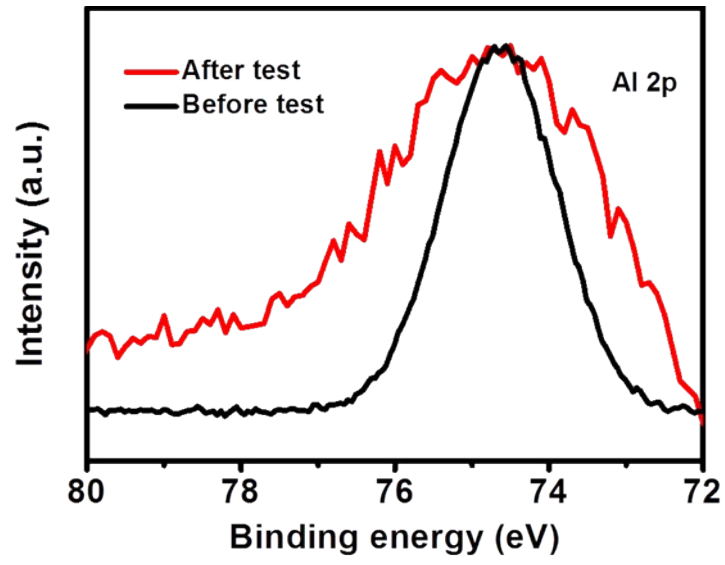


Fig. S17 XPS spectra of Al 2p for Ta<sub>3</sub>N<sub>5</sub>-AlO<sub>x</sub> photoanode through oxygen production test.

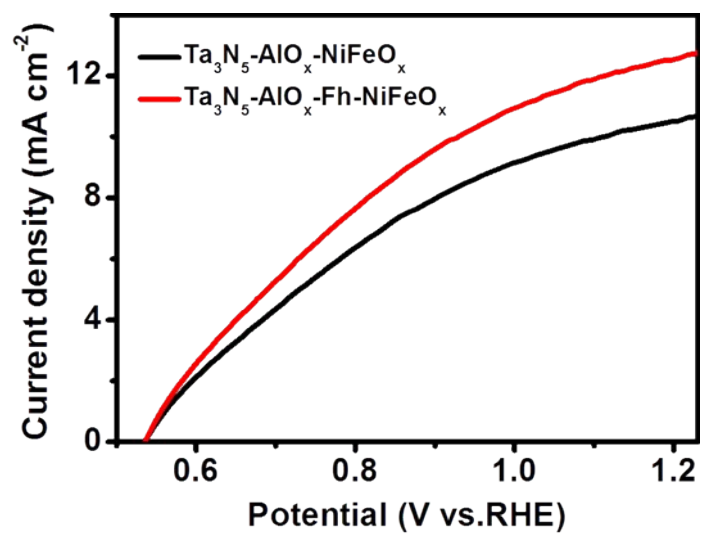


Fig. S18 Current-potential curves of Ta<sub>3</sub>N<sub>5</sub>-AlO<sub>x</sub>-NiFeO<sub>x</sub>, Ta<sub>3</sub>N<sub>5</sub>-AlO<sub>x</sub>-Fh-NiFeO<sub>x</sub> photoanodes in 1 M NaOH-0.5M H<sub>2</sub>O<sub>2</sub> solution.

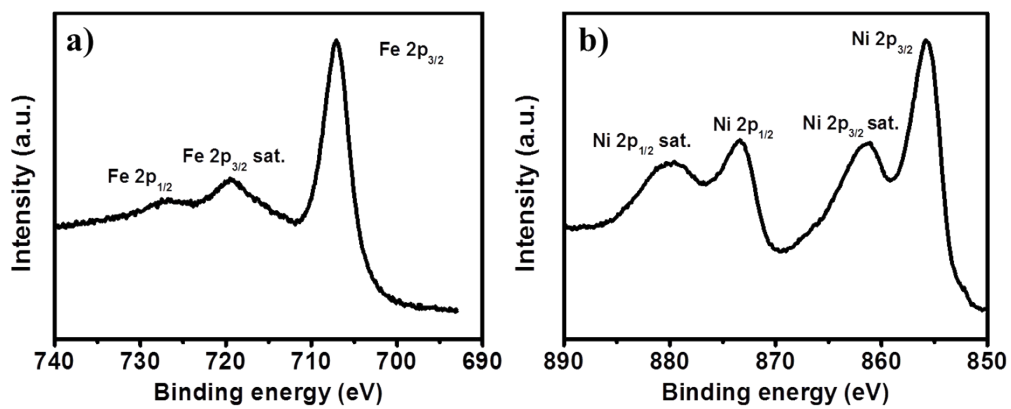
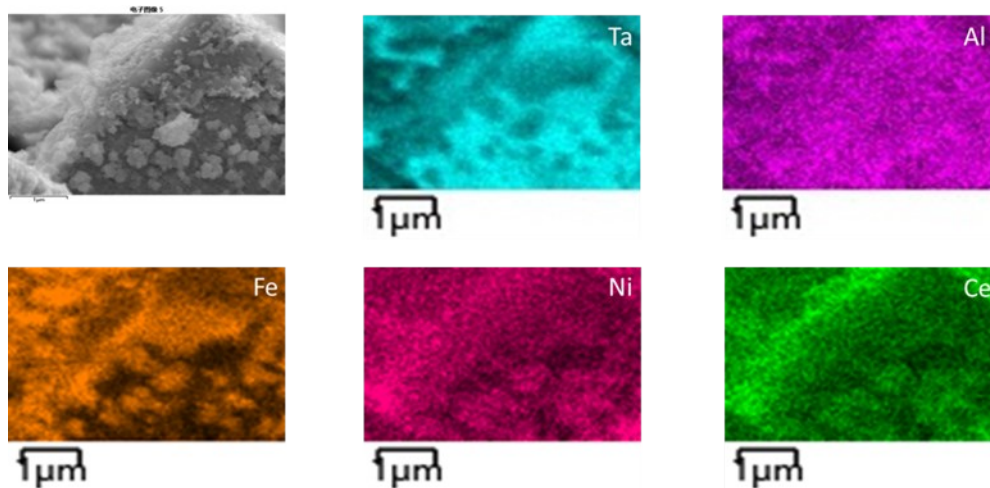


Fig. S19 XPS spectra of Fe 2p and Ni 2p for NiFeO<sub>x</sub>.



**Fig. S20** The high-resolution cross section SEM characterizations with EDX mapping of the Ta<sub>3</sub>N<sub>5</sub>-AlO<sub>x</sub>-Fh-NiFeO<sub>x</sub>-CeO<sub>x</sub> photoanode.

**Table S1** Representative Ta<sub>3</sub>N<sub>5</sub> based photoanode systems

Photoanode	J (mA cm <sup>-2</sup> ) at 1.23 V	ABPE (%)	Stability (h)	Ref.
Ba-Ta <sub>3</sub> N <sub>5</sub> /Co-Pi	6.7	1.5	0.5	1
Ta <sub>3</sub> N <sub>5</sub> /TiO <sub>x</sub> /Fh/Ni(OH) <sub>x</sub> /complex 1&2	12.1	2.5	0.5	2
Ta <sub>3</sub> N <sub>5</sub> -NR/FeNiO <sub>x</sub>	9.95	2.72	1	3
gradient-Mg: Ta <sub>3</sub> N <sub>5</sub> /NiCoFe-Bi	8.5	3.31	5	4
Ta <sub>3</sub> N <sub>5</sub> /AlO <sub>x</sub> /Fh/NiFeO <sub>x</sub> /CeO <sub>x</sub>	11.8	2.9	120	This work

## References

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- 2 G. Liu, S. Ye; P. Yan, et al. *Energy & Environmental Science*, 2016, 9, 1327.
- 3 Y. Pihosh, T. Minegishi, V. Nandal, et al. *Energy & Environmental Science*, 2020, 5, 1519.
- 4 Y. Xiao, C. Feng, J. Fu, et al. *Nature Catalysis*, 2020, 3, 932.